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INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No. NMTC-0771	Serial No. 10/098,713			
		Applicant MACLEAN, Kevin				
		Filing Date 3/15/2002	Group 2818 2825			
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<i>PR</i>	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um I-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.
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<i>PR</i>	Fu, C.C., et al., "Enhancement of Lithographic Patterns by Using Serif Features", IEEE, Transactions On Electron Devices, Vol. 38, No. 12, pp. 2599-2603, December 1991.
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						YES	NO
<i>JK</i>	JP 3-80525	4/5/1991	JP	H01L	21/27	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>JK</i>	WO 00/67074 A1	11/9/2000	WO	G03F	7/20	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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<i>JK</i>	WO 99/14636 A1	3/25/1999	WO	G03F	9/00	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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EXAMINER: Shallaka, Kirk

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